

'These devices perform well under the harsh conditions of our experimental procedures'

– Lawrence Berkeley National Lab User

SILICON NITRIDE TEMwindows

5 nm

1 square (25x25 μm) - SN100-A05Q00
 9 squares (50x50 μm) - SN100-A05Q33A
 2 slots (50x1500 μm)* - SN100-A05Q33L

FOR THE HIGHEST RESOLUTION IMAGING

10 nm

9 squares (100x100 μm) - SN100-A10Q33

FOR HIGH RESOLUTION WITH INCREASED ROBUSTNESS

20 nm

1 square (500x500 μm) - SN100-A20Q05
 9 squares (100x100 μm) - SN100-A20Q33

FOR EVERYDAY IMAGING

50 nm

1 square (100x100 μm) - SN100-A50Q01
 1 square (500x500 μm) - SN100-A50Q05
 1 square (1000x1000 μm) - SN100-A50Q10
 9 squares (100x100 μm) - SN100-A20Q33

FOR THE MOST DEMANDING CONDITIONS

Micro-porous

1 square (500x500 μm) - SN100-A50MP2Q05
 1 square (500x500 μm) - SN100-A20MP2Q05

FOR SUSPENSION OF MATERIALS & CRYO-EM

Plasma Cleanable

Silicon nitride grids can be vigorously plasma cleaned to remove organic contamination

Field to Field Uniformity

Less than 0.5 nm variation in film thickness across an entire production lot, not just a single window grid

Tolerates Temps >1000°C

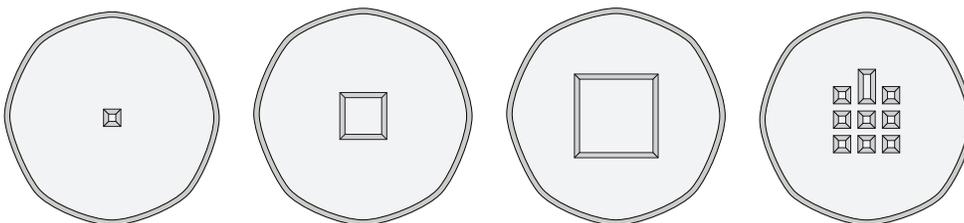
Supports use in environmental TEMs where dynamic processes are observed at high temperatures

Withstands Harsh Conditions

Provides an ideal balance of imaging resolution, chemical stability and mechanical strength

All window grids are sold in packages of 10

*Coated with 1 nm of ultrahigh purity carbon to minimize charging



- Silicon frames are 100 μm thick
- Grids fit standard 3 mm holders and most double tilt holders
- Packaged in clear gel-boxes for simpler sample preparation
- **Satisfaction Guaranteed**